

Patent claims

1. A method for producing a layer-like part (16) in which
 - the part (16) is created on a substrate (12) by coating of the substrate (12), the substrate (12) consisting of a shape memory alloy,
 - the substrate (12) coated with the part (16) is subjected to temperature control in such a way that the substrate undergoes a change in shape on account of the shape memory effect
 - and the part (16) is separated from the substrate band (12),characterized in that the microstructure texture of the substrate band is transferred to the layer-like part by the latter undergoing quasi-epitaxial growth.
2. The method as claimed in claim 1, characterized in that, in the case of the substrate (12), the one-way effect is used by the substrate being deformed before coating and heated after coating in such a way that the substrate goes over into its undeformed shape.
3. The method as claimed in claim 1, characterized in that, in the case of the substrate (12), the two-way effect is used by the substrate being subjected to temperature control before coating in such a way that it goes over into its one shape and the substrate being subjected to temperature control after coating in such a way that it goes over into its other shape.
4. The method as claimed in claim 3, characterized

in that the substrate (12) is alternately heated and cooled after coating in such a way that it alternately goes over into its one shape and its other shape.

5. A production facility with a substrate band (12) for producing a layer-like part (16) in sheet form, the substrate band (12) being led through a creating device (17) for the part and a temperature-controllable separating device (15) to obtain the part, and the substrate band consisting of a shape memory alloy, characterized in that the creating device is intended for quasi-epitaxial growth of the layer-like part onto the substrate band.
6. The production facility as claimed in claim 5, characterized in that the creating device is a facility for PVD coating or for galvanic coating.
7. The production facility as claimed in claim 5 or 6, characterized in that the creating device (17) is preceded by a deforming device, in particular a stretching device (23), for the substrate band.
8. The production facility as claimed in claim 5 or 6, characterized in that the creating device (17) is preceded by a temperature-controlling device (22) for the substrate band.
9. The production facility as claimed in one of claims 5 to 8, characterized

PCT/DE2004/002203
2003P13255WOUS

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in that the substrate band (12) is configured as an endless
belt circulating in the production facility.